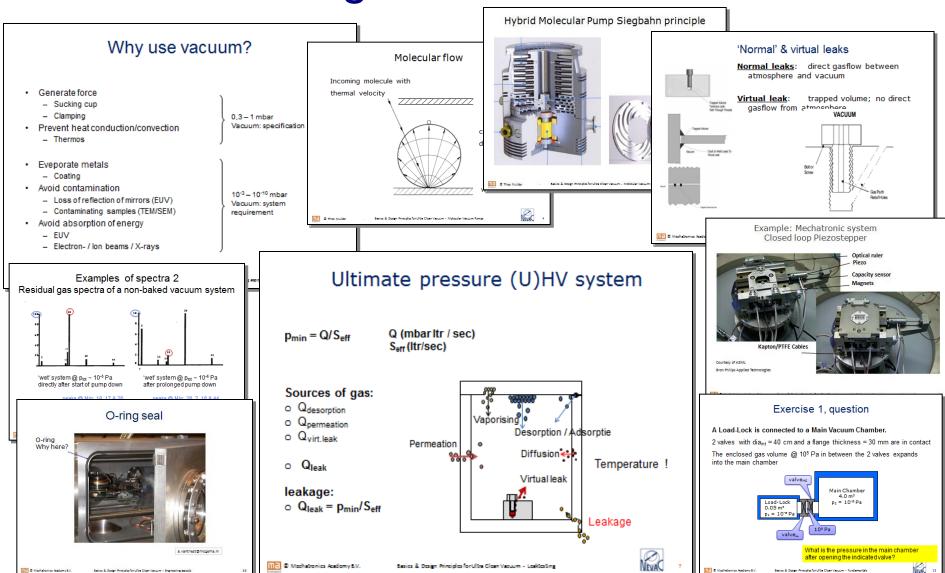
Basics & Design for Ultra Clean Vacuum







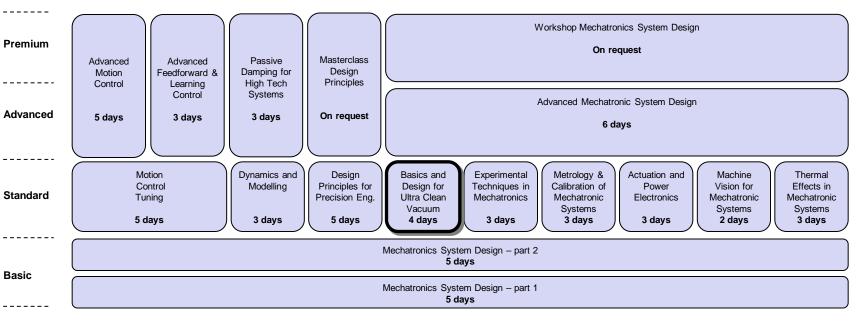
Contents

- Mechatronics Training Curriculum
- Details of Course Basics & Design for Ultra Clean Vacuum





Mechatronics Training Curriculum





Relevant partner trainings: Applied Optics, Electronics for nonelectrical engineers, System Architecture, Soft skills for technology professionals,

...

www.mechatronics-academy.nl





Mechatronics Academy

- In the past, many trainings were developed within Philips to train own staff, but the training center CTT stopped.
- Mechatronics Academy B.V. has been setup to provide continuity of the existing trainings and develop new trainings in the field of precision mechatronics. It is founded and run by:
 - Prof. Maarten Steinbuch
 - Prof. Jan van Eijk
 - Dr. Adrian Rankers
- We cooperate in the High Tech Institute consortium that provides sales, marketing and back office functions.





Basics & Design for Ultra Clean Vacuum





Course Director(s) / Trainers

Trainers

- Dr. Dick van Langeveld (NEVAC)
- Dr. Gesa Welker (TU Delft)
- David Schijve (NEVAC & VacTec)
- Thom Bijsterbosch, BSc (Settels Savenije van Amelsvoort)
- Ing. Mark Meuwese (Settels Savenije van Amelsvoort)
- Ir. Sven Pekelder (Settels Savenije van Amelsvoort)

Course Director(s)

- Ing. Mark Meuwese (Settels Savenije van Amelsvoort)
- Dr.ir A.M. Rankers (Mechatronics Academy)





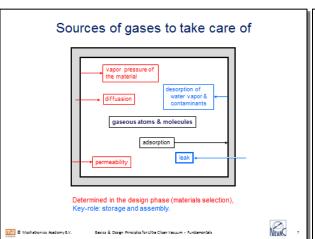
Program

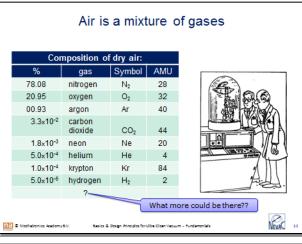
| Day | Topic | Presenter |
|-----|----------------------------------------------------------------------------------------------------|----------------------------------------------------------------|
| 1 | 09.00 Fundamentals / Flow of gases 12.30 Lunch 13.30 Total & Partial Pressure 17.00 End of day | Gesa Welker Dick van Langeveld |
| 2 | 09.00 Pumps / Applied RGA 12.30 Lunch 13.30 Leak Tightness (Theory & Practice) 17.00 End of day | David Schijve + Dick van Langeveld David Schijve |
| 3 | 09.00 Engineering Aspects 12.30 Lunch 13.30 Mechatronic Aspects 17.00 End of day | Dick van Langeveld Mark Meuwese |
| 4 | 09.00 Design for Qualification 12.30 Lunch 13.30 Vacuum Budgetting 17.00 End of day | Thom Bijsterbosch / Sven Pekelder Sven Pekelder + Mark Meuwese |

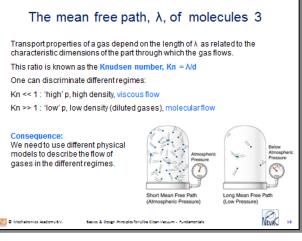


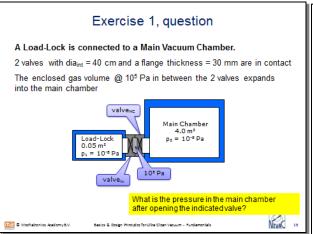


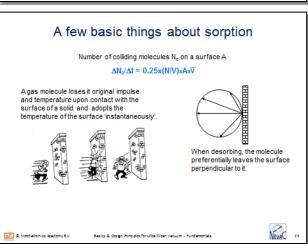
Day 1 (morning)

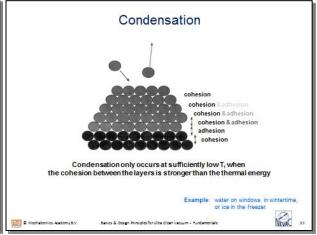








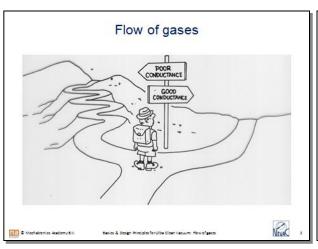


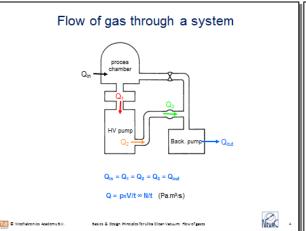


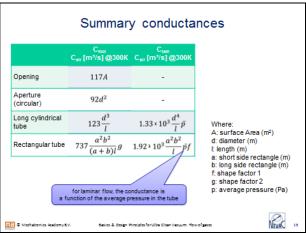


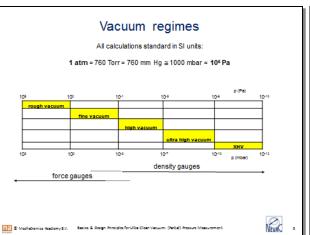


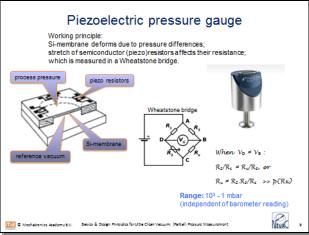
Day 1 (afternoon)

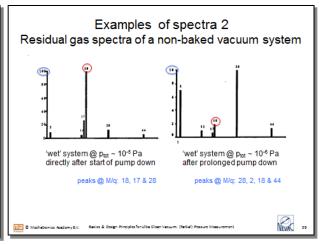








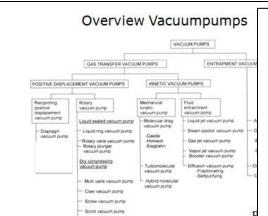








Day 2 (morning)



Types of compression

Isothermal compression:

Heat of compression is dissipated by the pump and its pumpmedium.

 $T_{gasin} = T_{gasout}$ So: $p_1 \times V_1 = p_2 \times V_2$ (Boyle's law)

With $p_1 = 10$ mbar, $V_1 = 100$ cm³ and $V_2 = 1$ cm³ it follows: $p_2 = 1000 \text{ r}$

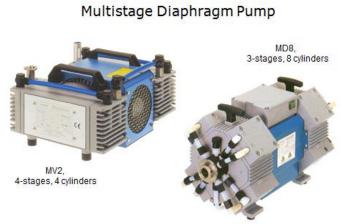
Adiabatic compression:

Heat of compression is fully transferred to the gas. $T_{gasout} > T_{gasin}$ So: $p_1 \times (V_1)^{1,4} = p_2 \times (V_2)^{1,4}$

Hybrid Molecular Pump Siegbahn principle

With $p_1 = 10$ mbar, $V_1 = 100$ cm³ and $V_2 = 1$ cm³ it follows $p_2 = 6309 \text{ n}$

Sasics & Design Principles for Ultra Clean Vacuum - Hydrocarbon Proc Sacking Pumps



Molecular flow

Sasies & Design Principles for Ulba Clean Vacuum - Molecular Vacuum Pu

Incoming molecule with thermal velocity



Theo Mulder Sesion & Dosien Principles for Ultra Close Vacuum - Molecular Vacuum Pump

Summary turbomolecular pump

Sasies & Ocsign Principles for Ultra Clean Vacuum - Hydrocarbon Prot Sacking Pumps

A TMP needs always a backing pump

Critical backing pressure of 10 Pa (10⁻¹ mbar)

Compression ratio increases with increasing molecular mass

As long as the oil- or grease lubricated TMP is in operation: no backstreaming of hydrocarbons

If an oil- or grease lubricated TMP is not in operation: TMP should always be vented



NEVAC

Sasics & Doign Principles for Ultra Clean Vacuum - Molecular Vacuum Pump



NevaC



Day 2 (afternoon)

Permeation

10-2 mbarl/s

10⁻² mbarl/s

10⁻³ mbarl/s

10⁻⁵ mbarl/s

10-11 mbarl/s

NEVAC

Ultimate pressure (U)HV system

Vaporisino

Desorption / Adsorptie

Diffusion ***

Virtual leak

 $p_{min} = Q/S_{eff}$ Q (mbarltr / sec) S_{eff} (Itr/sec)

Sources of gas:

- o Q_{desorption}
- Q_{permeation}

leakage:

Q_{leak} = p_{min}/S_{eff}

Leaktesting

Why?

- R&D: (U)HV systems
 - Lowest possible pressure!
- Quality certification ! Industry:

Example:

Gascilinder Airbag need 10 yrs operati Qualification: pressure-drop less < 0,5

= V. Δp/ Δt = 0.2 ltr * 500 / 10*365*24*3.60 = 3.2*10⁻⁷ mbar ltr / sec

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Residual Gas Analysis

- (high)vacuumsystems
- analysing the gascomposition devided by molecular mass
- measuring partial pressures
- possibly leaktesting:
 - peak for N2 and O2 at 4:1 - use heliumpeak

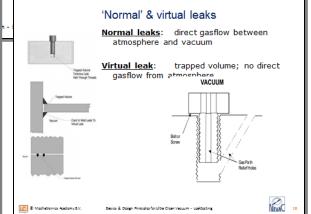


Leaktesting methods

- Pressure-rise test
- Simple, direct, no location - Soap or foam
- overpressure, location, low sensitivity
- Alcohol/acetone/helium/argon with pirani
- underpressure, location, low sensitivity Overpressure test, specific gas
- overpressure, location, medium sensitivity
- underpressure, location, very high sensitivity
- Residual Gas Analysis 10⁻¹¹ mbarl/s

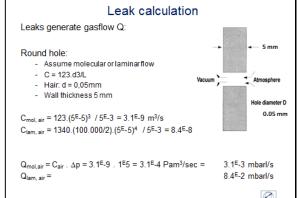
Sesion & Dosign Principles for Life Clean Vacuum - Looktesting

- highvacuum, gas spectrum, very high sensitivity



Temperature

Leakage



Senior & Dorigo Priorigios fortifica Close Vanuem - Loskicatio

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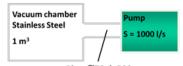
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Day 3 (morning)

Why use vacuum? · Generate force - Sucking cup Clamping 0,3-1 mbar Vacuum: specific · Prevent heat conduction/convection - Thermos · Eveporate metals - Coating Avoid contamination 10⁻³ - 10⁻¹⁰ mbar Loss of reflection of mirrors (EUV) Vacuum: system - Contaminating samples (TEM/SEM) requirement Avoid absorption of energy - EUV - Electron- / Ion beams / X-rays □ E Mochatronics Academy S.V. Sesies & Design Principles for Ultra Clean Vacuum - Engineering aspects

Pumping speed

- · What will be the effective pumping speed at the entrance of t
- What will be the end pressure, when Q=10⁻³ mbar.L/s
- What will be the pump-down time to reach 10⁻⁴ mbar?



O-ring seal

Pipe Ø50, I=500mm

□□□
 Mochatronics Academy S.V. Sasics & Ocsign Principles for Ultra Clean Vacuum - Engineering aspects

O-ring

III @ Mochatronics Academy 8.V.

Why here?

Theoretical pump down curve Pressure (Torr) Volume ~ exp(-t) 10 10.1 10-3 Outgassing ~ t-1 10-5 Diffusion $\sim t^{-1/2}$ 10-7 Permeation 10^{-9} 10-11 10-13 101 103 105 107 109 1011 1013 1015 1017 Time (s)

Gasloads 1. Leaks a. Real leaks b. Virtual leaks Desorption/Outgassing 3. Diffusion 4. Permeation 5. Evaporation 6. Back streaming pump III @ Mochatronics Academy S.V. Sanier & Design Principles for Lifes Close Vanuer - Registerring apperts

washing machine

with soap

III @ Mochatronics Academy S.V.

1 mbar

Precleaning with tap water

Cleaning procedures, removing oil & grease with water & soap

> Cleaning step neutralize rinse with demi-water

Drv Bake out @ 120 - 200°C in vacuum

III @ Mochatronics Academy S.V.

a.vantriest@mocema

Basics & Design Principles for Ultra Clean Vacuum - Engineering aspects

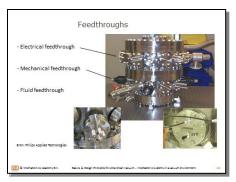
1.10⁻¹⁰ mbar

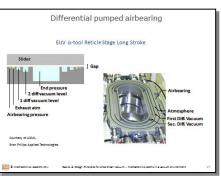
ultrasonic

with soap

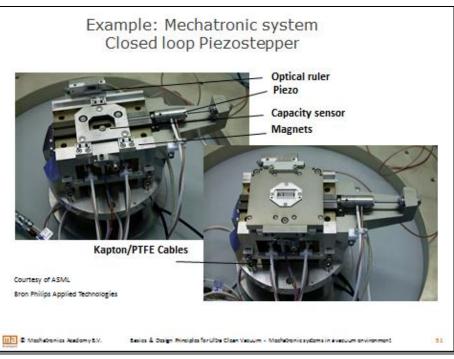
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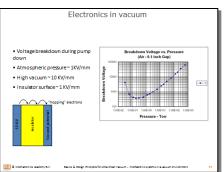
Day 3 (afternoon)

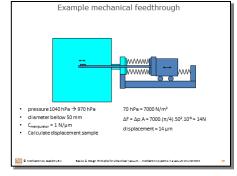


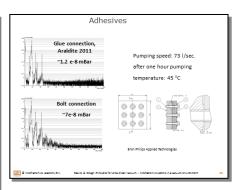


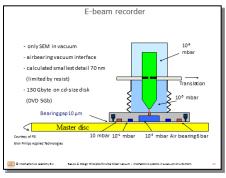


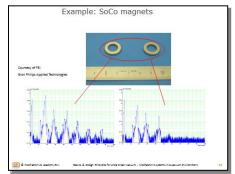
















Day 4 (morning)

Qualification

- Medium RGA qualification system Philips Apptech
- · Typical application: (sub)assemblies
- Background ≈1% of product specification

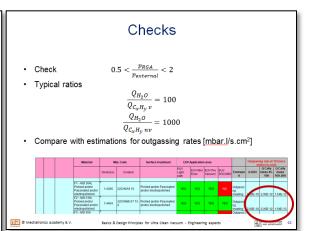
$$- p_{H_2O} \approx 10^{-10} mbar$$

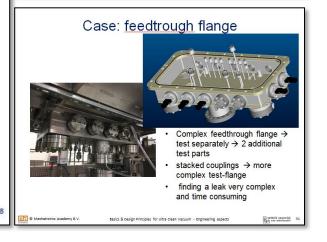




Basics & Design Principles for Ultra Clean Vacuum - Engineering aspects

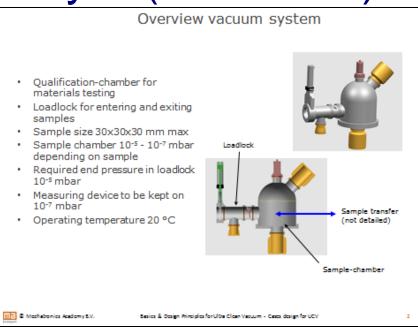
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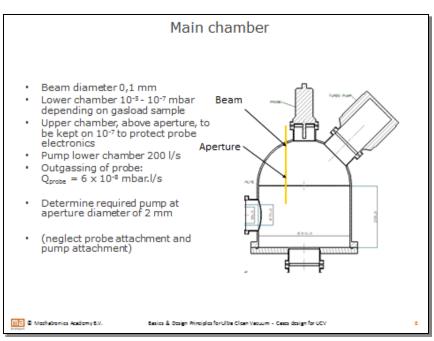


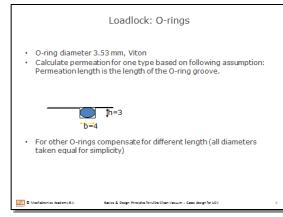


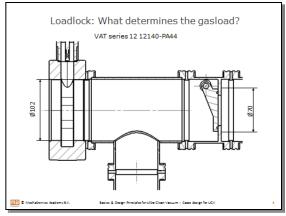


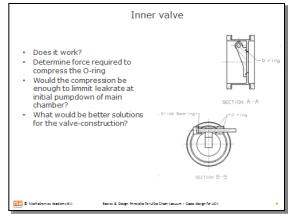
Day 4 (afternoon)















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